



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kenji NISHI

Application No.: 08/994,758

Filed: December 19, 1997

For: PROJECTION EXPOSURE APPARATUS

Group Art Unit: 2851

Examiner: A. Mathews

Docket No.: 110157.99

#291
10/11/01
aga

AMENDMENT IN REISSUE APPLICATION

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the Office Action dated March 28, 2001, the shortened statutory period for reply being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claims 10-12, 48, 79, 108, 143-149, 156-163, 168-171 and 179-188

without prejudice to or disclaimer of the subject matter contained therein.

Please replace claims 9, 13, 15, 29, 30, 33, 36, 37, 43, 49-51, 68, 80, 81, 96, 97, 103, 109-111, 130, 131, 135, 137, 138, 141 and 142 as follows:

9. (Twice Amended) A scanning exposure apparatus comprising:

a projection optical system for projecting a pattern image of a mask onto a

photosensitive substrate;

a scanning system for synchronously scanning [a] the mask and [a] the

photosensitive substrate for scanning exposure, wherein said scanning system includes a

mask stage for scanning the mask in a direction perpendicular to an optical axis of said

Sub
171,173

51